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- HIROSE, Jun  
Nakakoma-gun Yamanashi 409-3865 (JP)
- NARUSHIMA, Masaki;  
Higashiyatsushiro, Yamanashi 406-0853 (JP)

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(74) Representative: HOFFMANN - EITLE  
Patent- und Rechtsanwälte  
Arabellastrasse 4  
81925 München (DE)

(71) Applicant: TOKYO ELECTRON LIMITED  
Minato-ku, Tokyo 107-8481 (JP)

(72) Inventors:  
• OZAWA, Jun  
Nakakoma-gun, Yamanashi 400-0113 (JP)

(54) VACUUM PROCESSING SYSTEM

(57) A vacuum process system comprises: a load port on which an object to be processed is set; a common transfer chamber disposed adjacent to the load port, having an internal space set at an atmospheric pressure level, and including a first transfer device that is movable and transfers the object into/from the load port, the first transfer device being disposed within the internal space; and a process unit having one process chamber for subjecting the object to a predetermined process, and a vacuum transfer chamber connected to the process chamber, having an internal space set at a vacuum pressure level, and including a second transfer device for transferring the object into/from the process chamber, the second transfer device being disposed within the internal space. The process units are individually connected to the common transfer chamber such that the process units are substantially parallel to each other. The vacuum chamber of each process unit is connected to the common transfer chamber. Each process unit extends linearly in a direction substantially perpendicular to the common transfer chamber. The object is transferred into/from the vacuum transfer chamber by means of the first transfer device.

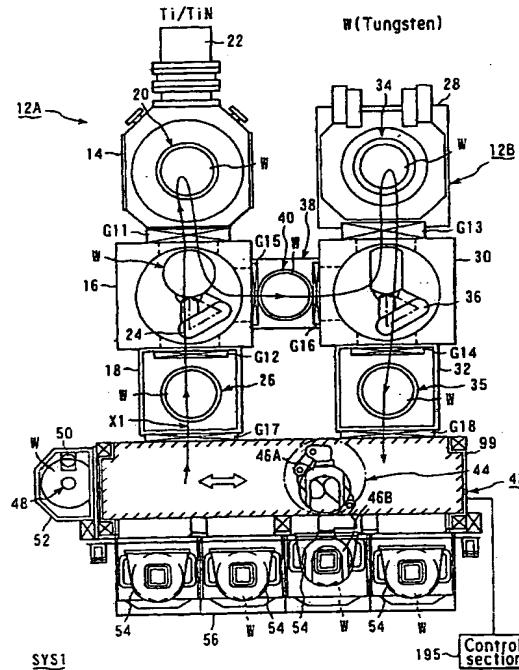


FIG. 1